Supplementary Information

Synthesis of Cu(OH)₂ and CuO nanotubes arrays on a silicon wafer

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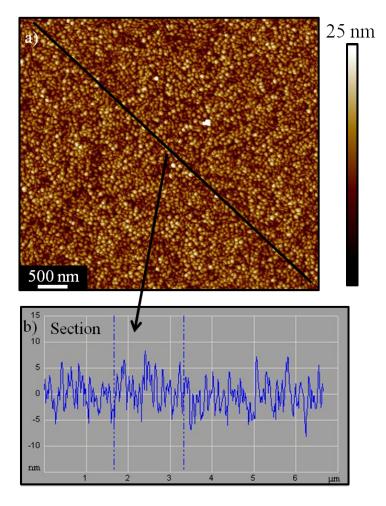


Fig.S1: **Roughness of the copper layer.** AFM a) image and b) cross section of the surface of the copper layer deposited on the top of a silicon wafer covered by 30 nm of titanium.

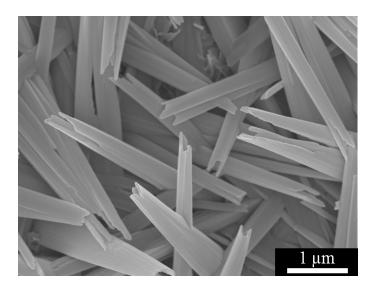


Fig.S2: Growth of Cu(OH)₂ tubes by using only the first reaction. SEM image of Cu(OH)₂ tubes grown on the copper layer when the wafer was exposed only to the first reaction during 5 hours.

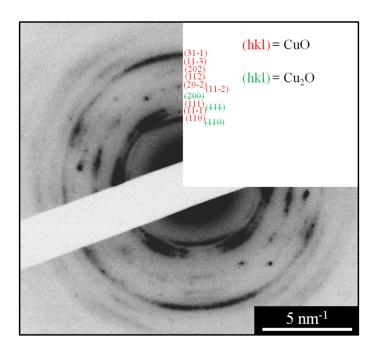


Fig.S3: Origin of Cu_2O in the annealed samples. Electronic diffraction of a single tube annealed under a N_2 gas flow at 200°C during 1 h.